

Appl. No.: 10/706,863  
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Amdt. dated January 4, 2005

Amendments to the Specification:

Please amend the second paragraph, on page <sup>2</sup>~~6~~, line 22 as follows:

In a first method for forming a porous film as described in Japanese Patent Provisional Publication Nos. 2001-2993, ~~[[13]]2001-98218~~ and ~~[[13]]2001-115021~~, a composition comprising a thermally unstable organic resin component and a siloxane polymer is synthesized, is applied on the substrate to form a coating film, and then treated thermally for decomposing and volatilizing the organic resin component so that a number of pores are formed in the film.

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7/10/06